



# Insights into Characterization of Large Area Graphene along the Process Chain

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## Agenda

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- SURAGUS as company and as EU Gladiator
- Challenges for industrial Graphene applications
- Example application graphene as TCM
  - Quality characteristics and common defects
  - Electrical characterization of Graphene
  - Defectoscopy - information added by sheet resistance imaging
- Summary and conclusion



# Company - SURAGUS GmbH

SURface ArGUS = Surface guard

## Technology

HF Eddy current-based testing solutions for innovative materials

## Location and Presence

R&D and production in Germany, Dresden, near Airport and A14  
EddyCus systems are present on six continents

## Ownership

LayTec and SURAGUS Group (> 2200 measurement systems worldwide)

## Applications

Quality assurance of functional thin-films

## Values

Accurate and reliable solutions

Smart solutions (inline reverse calibration, automated self-reference, temperature stabilized)

High technical flexibility (various gap sizes, different sensor setups, traverse and fixed)

Excellent service (Close contact / short response times)





## SURAGUS as EU Gladiator & Associated Flagship Member



<http://graphene-gladiator.eu/>

- ▶ Fraunhofer COMEDD (Germany)
- ▶ Graphenea S.A. (Spain)
- ▶ Danmarks Tekniske Universiteit (Denmark)
- ▶ Horiba Jobin Yvon S.A.S. (France)
- ▶ AIXTRON SE (Germany)
- ▶ AIXTRON Ltd. (United Kingdom)
- ▶ Suragus GmbH (Germany)
- ▶ Commissariat à l'énergie atomique et aux énergies alternatives (France)
- ▶ Amcor Flexibles Kreuzlingen AG (Switzerland)
- ▶ Amcor Flexibles Singen GmbH (Germany)
- ▶ Leibniz-Institut für Oberflächenmodifikation (Germany)
- ▶ Det National Forskningscenter Forarbejdsmiljø (Denmark)
- ▶ Aristotelio Panepistimio Thessalonikis (Greece)
- ▶ Organic Electronic Technologies (Greece)
- ▶ Amanuensis GmbH (Switzerland)



# Challenges the Industry Is Facing from an Commercial/Industrial Application Point of View

The key challenge is finding an application where Graphene can achieve a superior and competitive set of characteristics

## Physical Characteristics

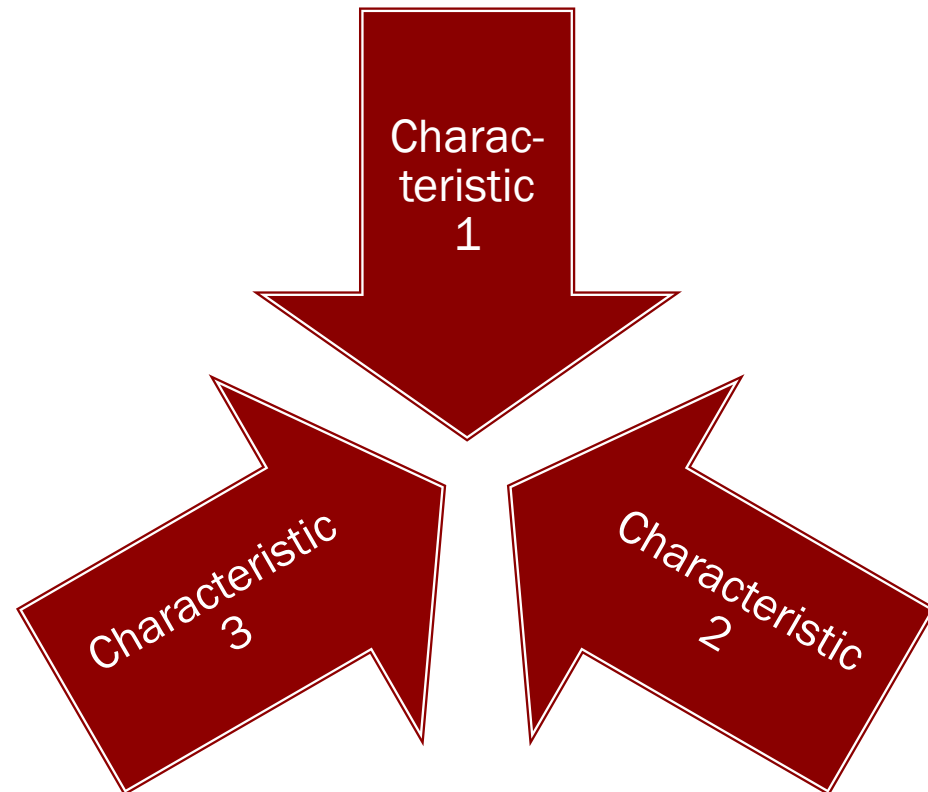
- Electrical properties
- Mechanical properties
- Chemical properties
- Optical properties
- Etc.

## Soft characteristics

- Ability for flexible substrates
- Stable over time

## Financial Characteristics

- Cost per performance



# Challenges the Industry Is Facing from an Commercial/Industrial Application Point of View



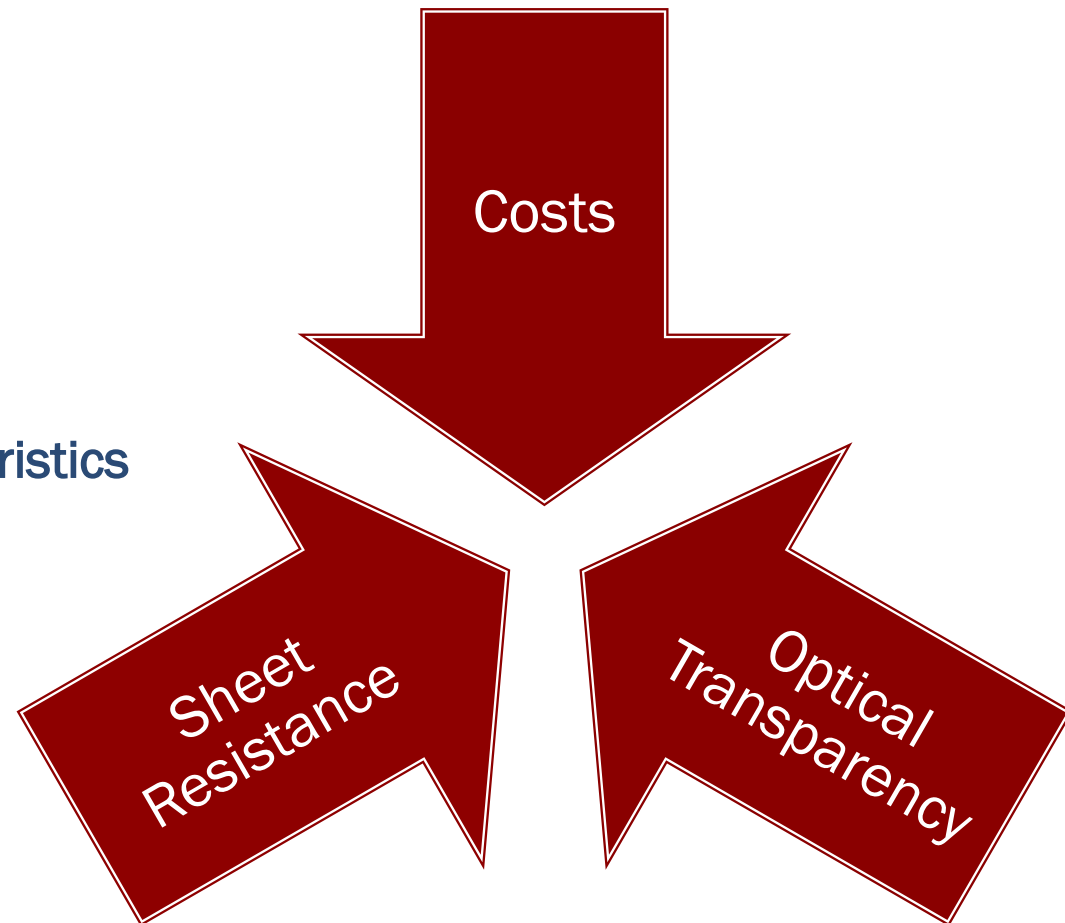
Example: Graphene as transparent electrode

## ▶ Requirements/ trends

- Low cost
- Low sheet resistance
- High transparency

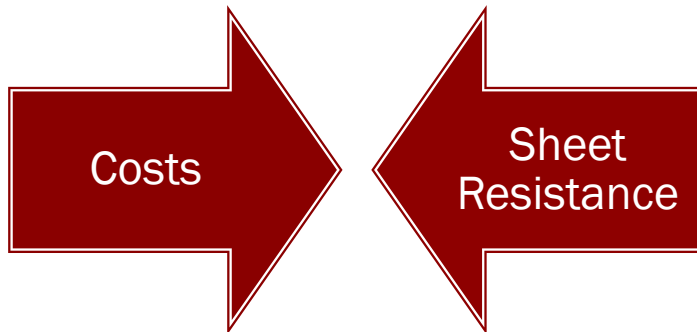
## ▶ Beneficial/ further characteristics

- Ability for flexible substrates
- Low aging effects



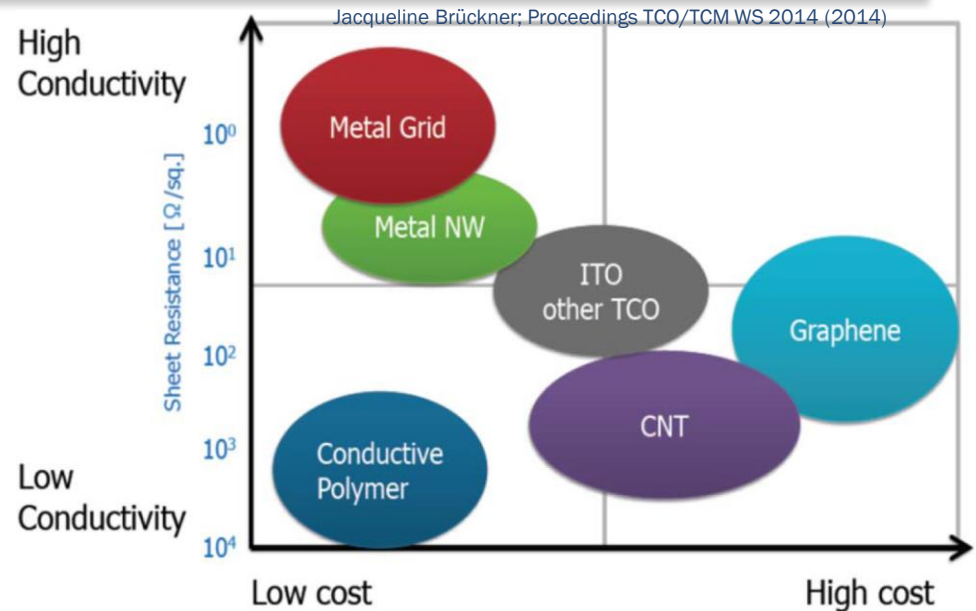


# Drivers & Challenges in Manufacturing



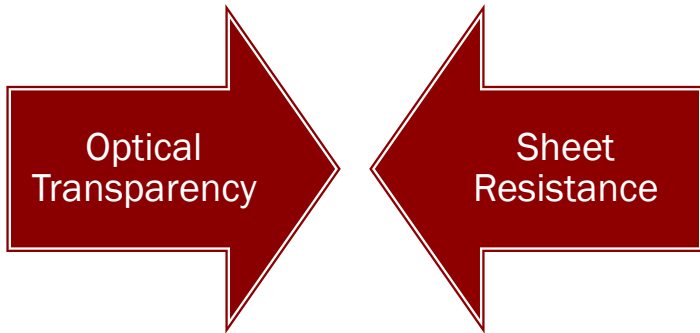
## Cost improvement

- Larger substrate sizes / gapless production/R2R
- Higher throughput due to higher deposition/growth rate
- Cheaper processes: atmospheric pressure, low temperature
- More automation / continuous processes?
- Optimized material input e.g. reuse of growth substrates



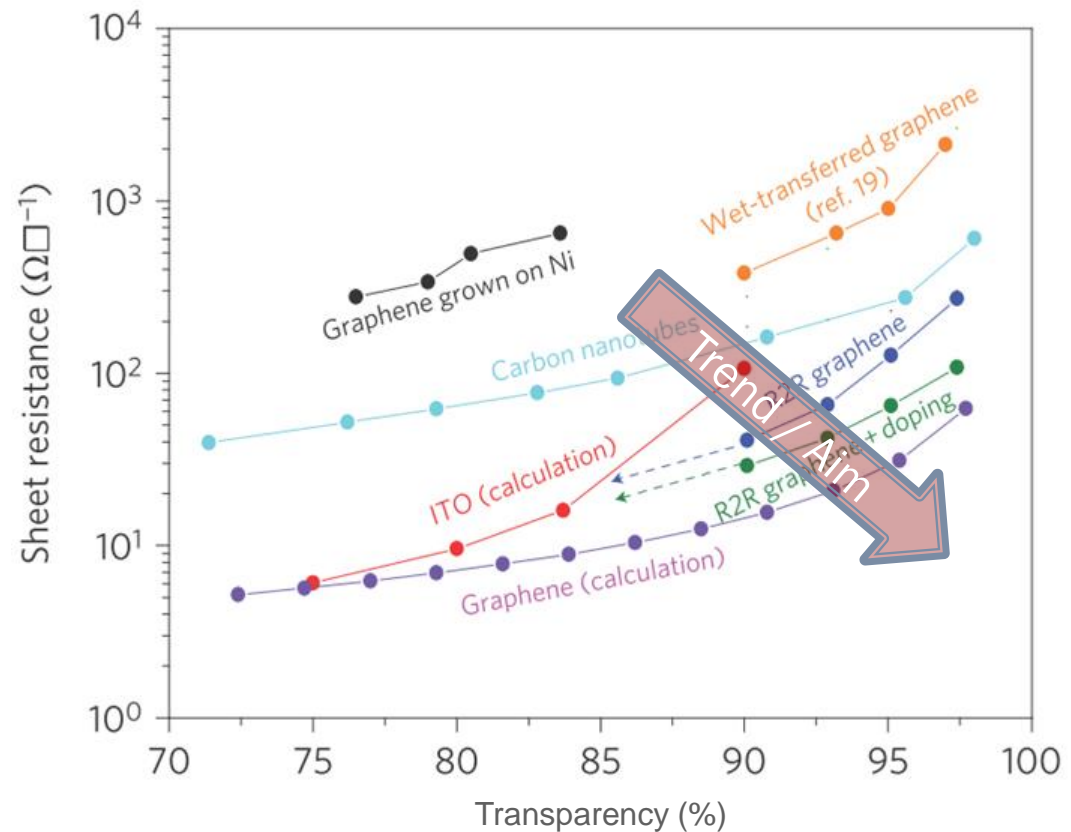


# Graphene as Transparent Electrode



## Main Parameter

- Low boundary rate / monocrystalline
- Physical integrity
- Doping
- Annealing
- Stacking, patching
- Defect-freeness



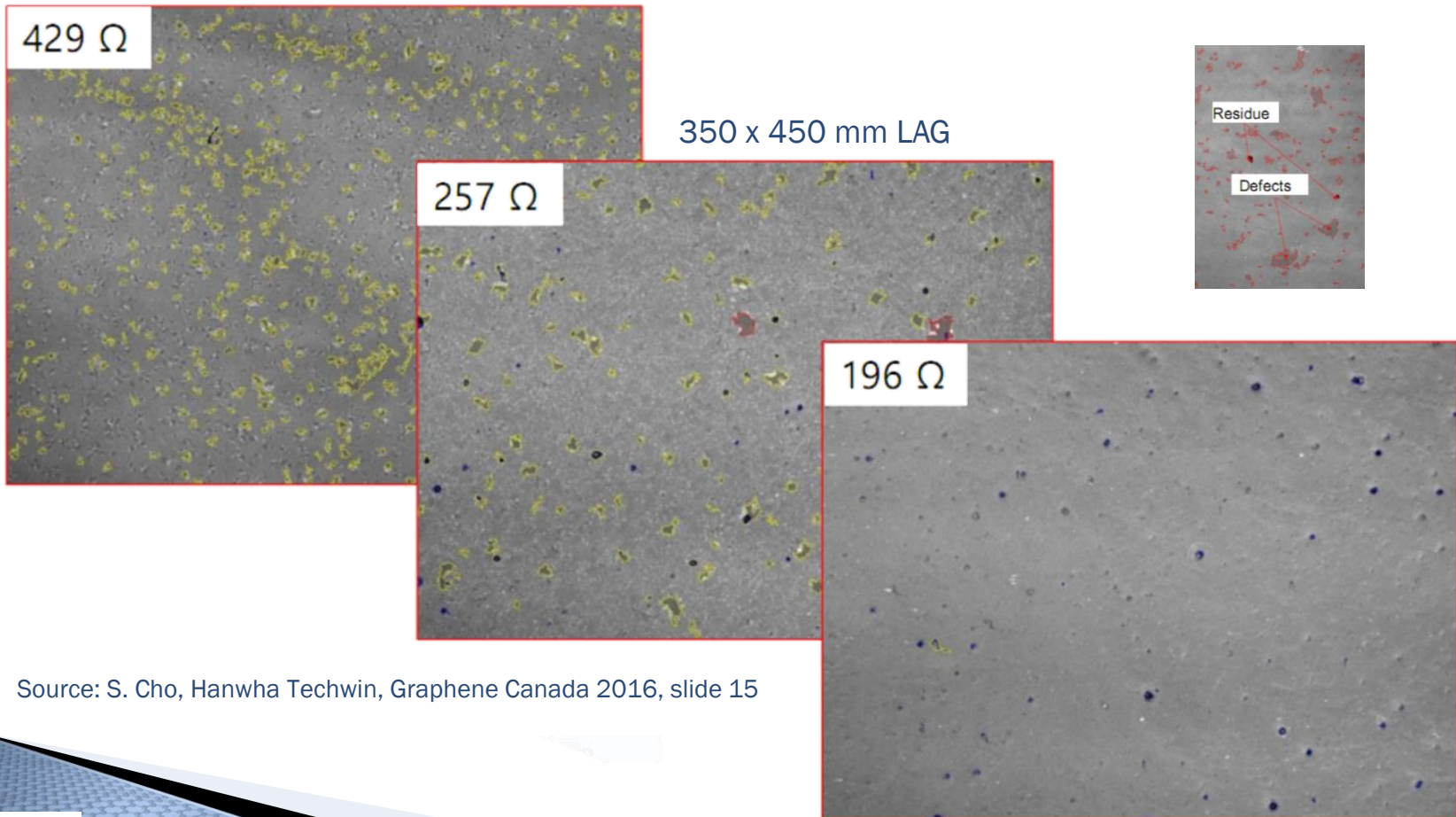
S. Bae et al. Nature Nano. 5, 571 (2010)





## Effects of Defects to the Sheet Resistance

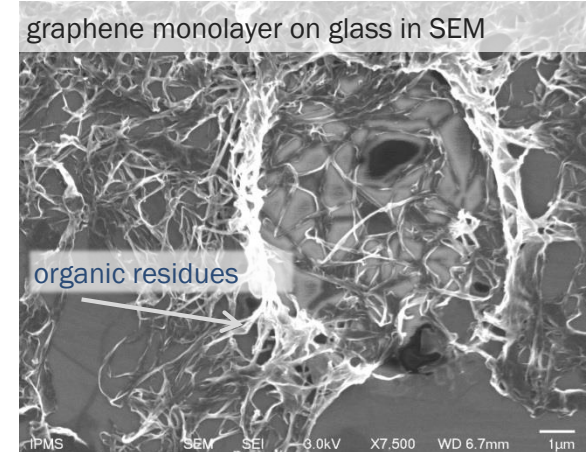
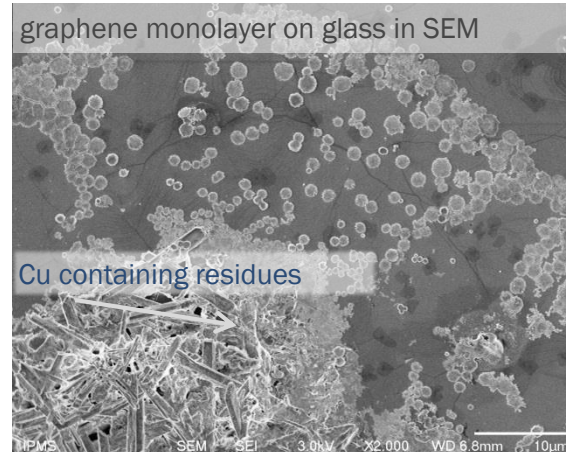
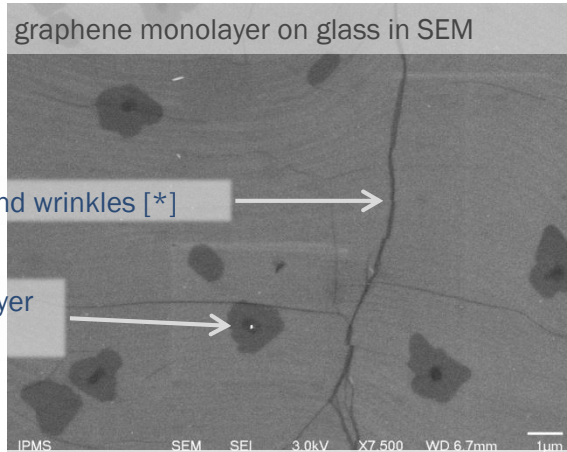
- The defect density significantly affects the sheet resistance



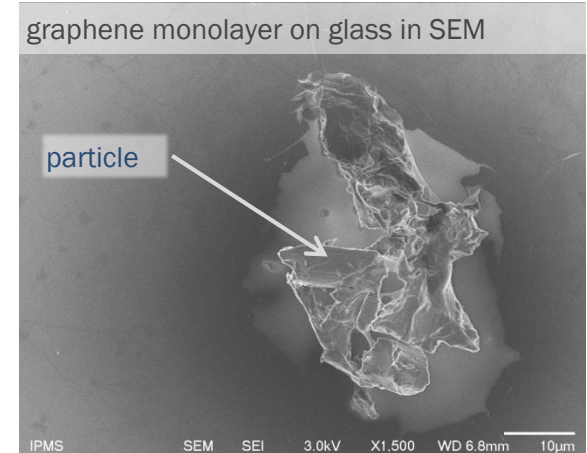
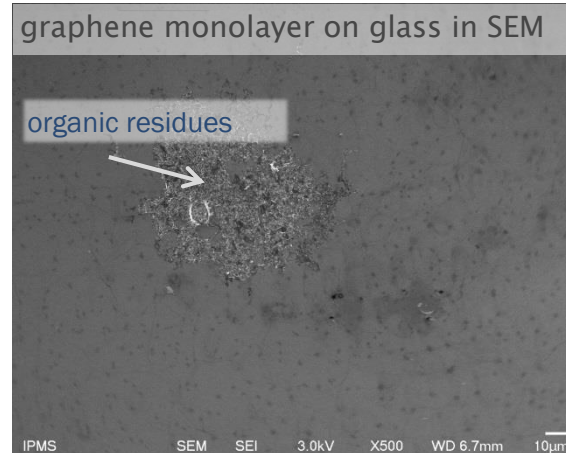
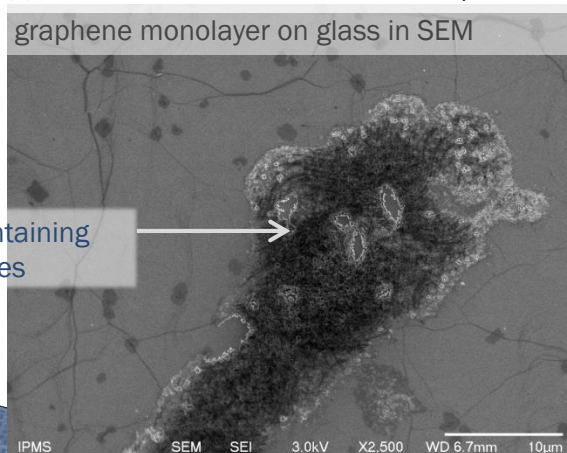
Source: S. Cho, Hanwha Techwin, Graphene Canada 2016, slide 15



# Typical Defects in Graphene



[\*] Zhu et al., *Structure and Electronic Transport in Graphene Wrinkles*, Nature Nanoletters, 2012

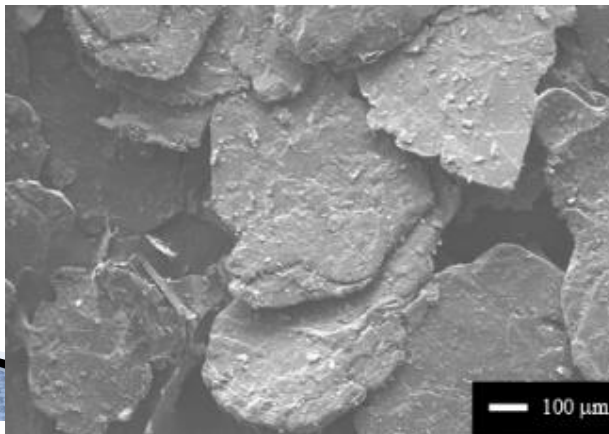
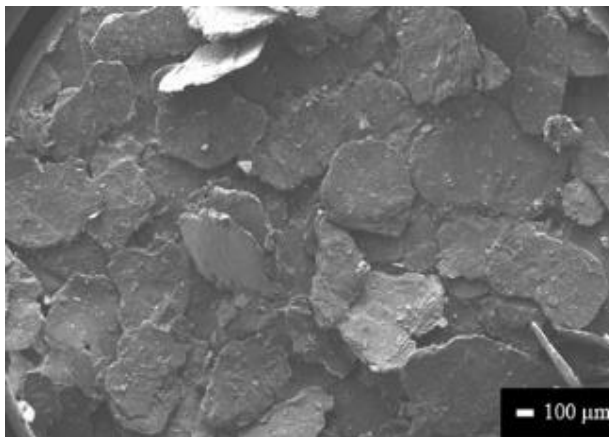


Source: D. Waynolds et al., Fraunhofer FEP



## Properties and Common Defects

- Flake size



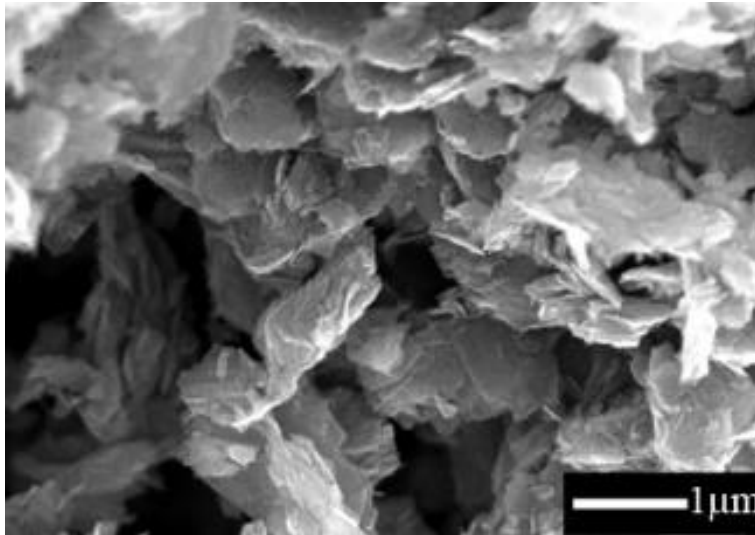
Effect on  
sheet resistance

Source: Graphene-supermarket.com



## Properties and Common Defects

- Stacking angle and stacking density



Effect on  
sheet resistance

Source: Graphene-supermarket.com



## Properties and Common Defects

- Monolayer / multilayer Graphene
- Polycrystalline graphene / flake size
- Contaminations, particles and residues
- Doping and doping homogeneity
- Stacking angle and stacking density
- Line defects, wrinkles, holes, missing Graphene

Significant effects  
on  
sheet resistance



# Quality Characteristics of Graphene as TCM

Thickness / # of layers	Defect freeness	Sheet Resistance	Optical transparency	Robustness
<ul style="list-style-type: none"> <li>▪ Homogeneity</li> </ul>	<ul style="list-style-type: none"> <li>▪ Cracks/ gaps, tearing</li> <li>▪ Holes Folds/wrinkles</li> <li>▪ Impurities (before and after doping)</li> <li>▪ Point defects, vacancies, rotated bonds</li> <li>▪ Dopant atoms</li> <li>▪ Contaminant particles from catalysts and CVD process</li> <li>▪ Missing Interlayer conductivity</li> <li>▪ Not connected flakes</li> <li>▪ Too low overlap after patching</li> <li>▪ Multilayer regions</li> </ul>	<ul style="list-style-type: none"> <li>▪ Quantification in a range of 10 Ohm/sq to 3000 Ohm/sq</li> <li>▪ Homogeneity               <ul style="list-style-type: none"> <li>▪ How to define it</li> </ul> </li> </ul>	<ul style="list-style-type: none"> <li>▪ Optical transparency from UV up to IR wave lengths</li> <li>▪ Quantification</li> <li>▪ Range: Transmittance from 80 – 97.7% or absorbance</li> <li>▪ Homogeneity</li> <li>▪ How to define it</li> <li>▪ Other optical parameters such as haze</li> </ul>	<ul style="list-style-type: none"> <li>▪ Stability/Aging</li> <li>▪ Ability of flexible substrates</li> <li>▪ Heat resistance</li> </ul>

- How to define homogeneity and defect density?
- By result / resistance for TCM?



# Metrology for Graphene

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## Commonly applied testing technology

- Raman
- TEM and SEM
- High magnification optical microscopes
- Optical spectrometer (reflection and transmission)
- 4PP
- Eddy Current
- Van der Pauw
- Terahertz spectroscopy
- Mechanical testing
- Others



# Quality Determination of Graphene as Transparent Electrode

- Sheet resistance
  - 44P
  - Van der Pauw
  - Eddy Current
- Optical transparency
  - Optical transmission measurement



Non-contact



# Electrical Testing of Graphene



## 4-point-probe testing

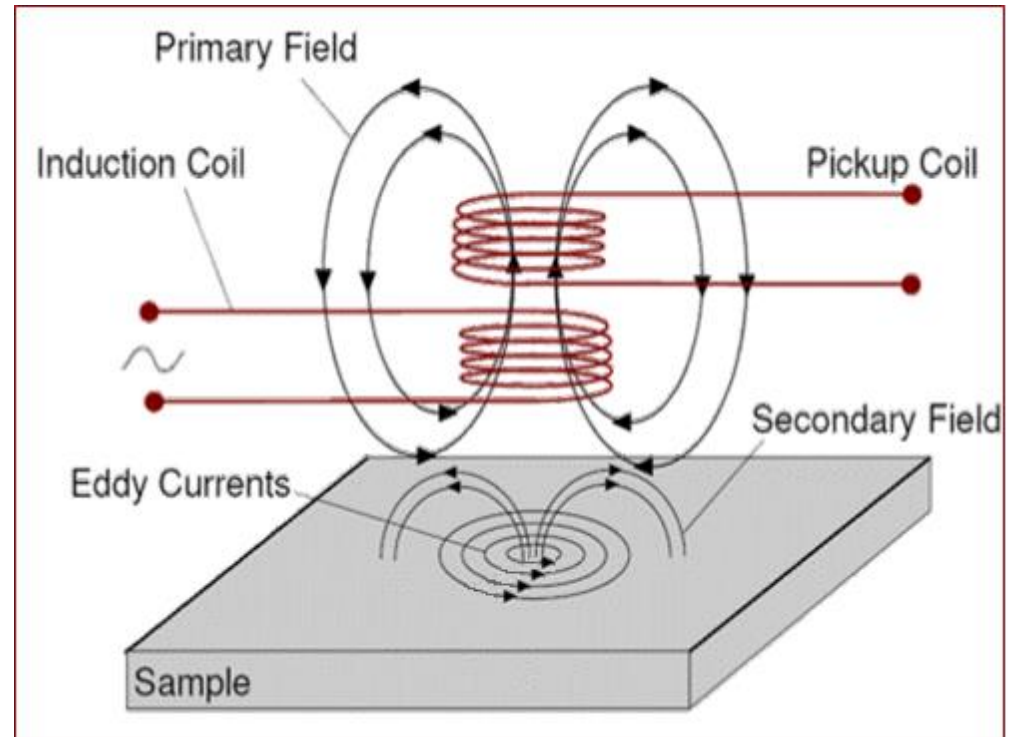
- Contact quality artifacts
- Possible damage to sensitive layers
- No measurement of encapsulated films
- Wearing of probe with time

## Non-contact eddy current testing

- No influence of contact quality
- No harm or artifacts to sensitive films
- Measurement of encapsulated films
- Very fast measurement
- High resolution mapping
- Inline measurement possible



## Sheet Resistance Measurement by Eddy Current



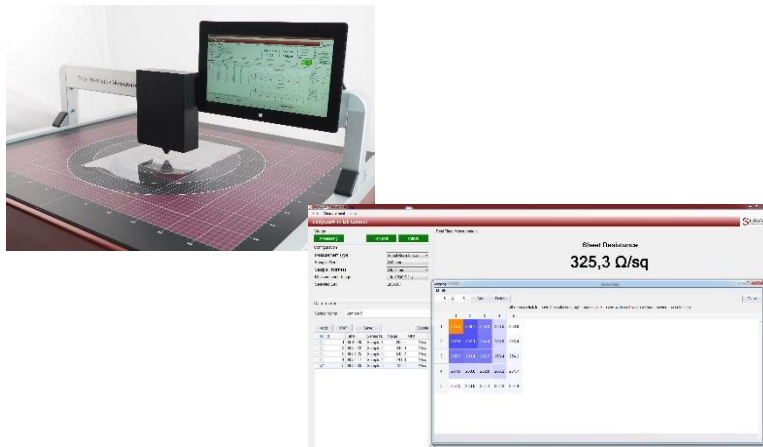
- + Non-contact
- + High sample rate
- + High sensitivity

- Limited to conductive materials



# General Testing Setups

## Single Point Testing

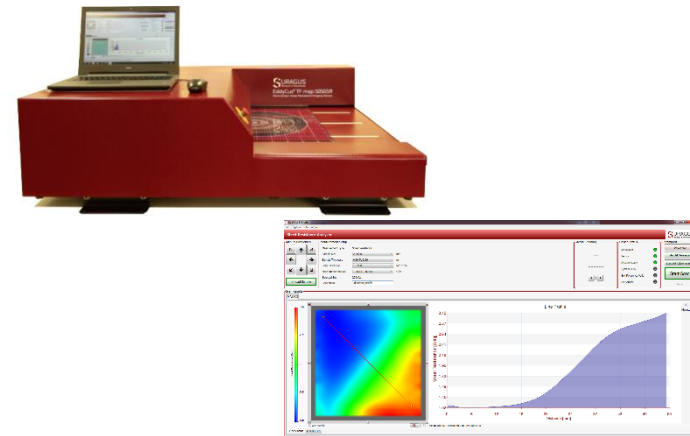


### EddyCus® TF lab Series

#### Sheet resistance & OT

- After transfer
- Doping
- Annealing
- Aging

## Imaging Solutions



### EddyCus® TF map Series

#### Sheet resistance & OT imaging

#### Defect detection

- Impurities
- Deposition effects
- Many more



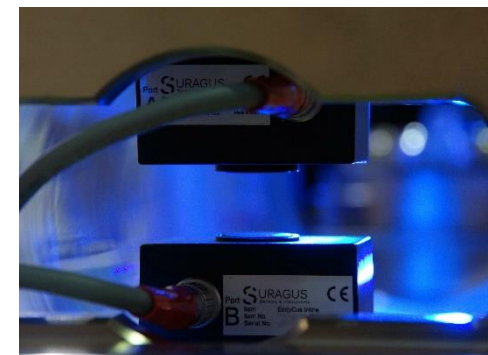
# General Testing Setups

## Inline Testing

### EddyCus® TF inline Series

#### Sheet resistance & OT

- Concept for inline graphene manufacturing and inline testing is currently created



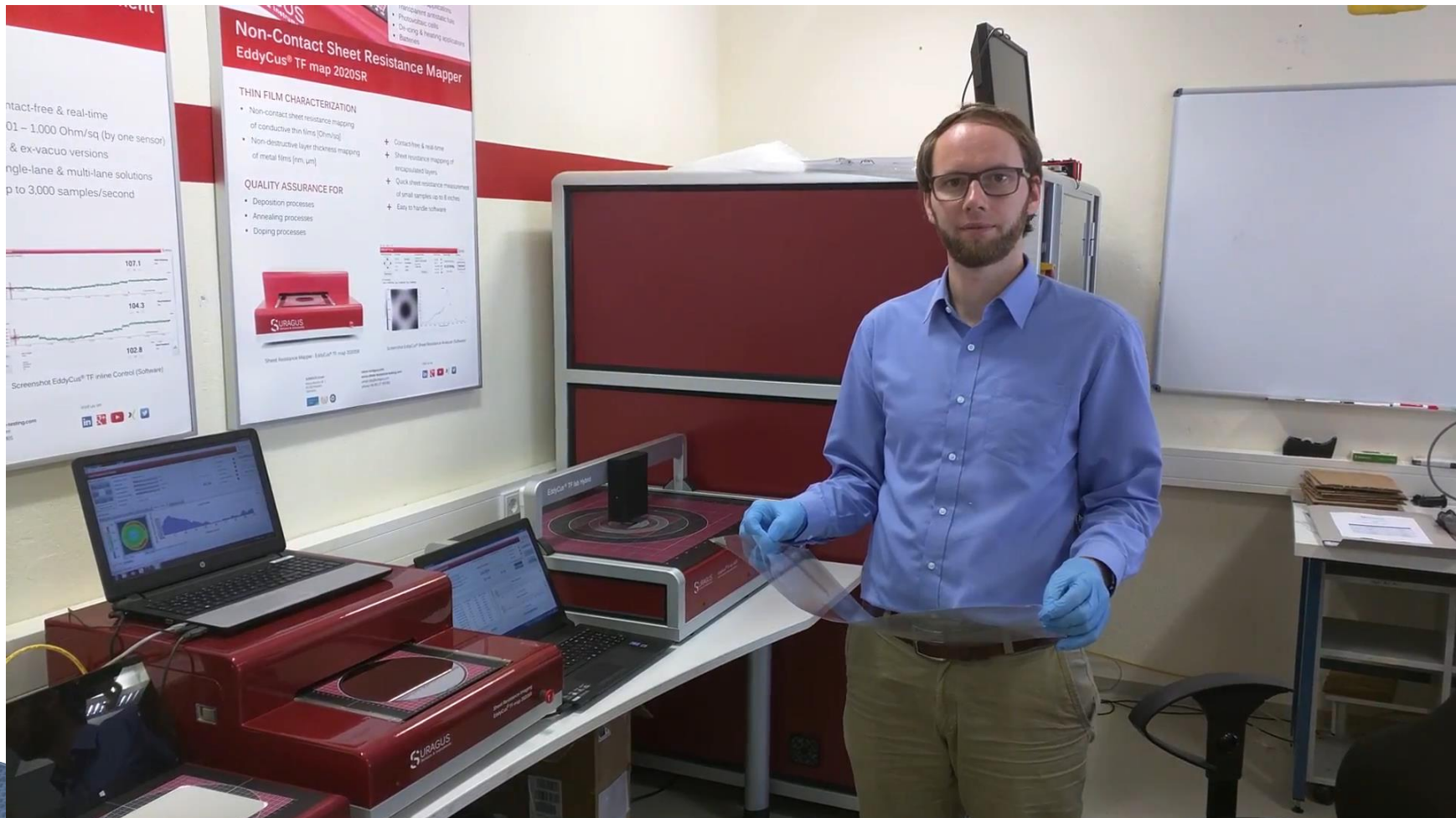


## Demonstration – Manual Mapping



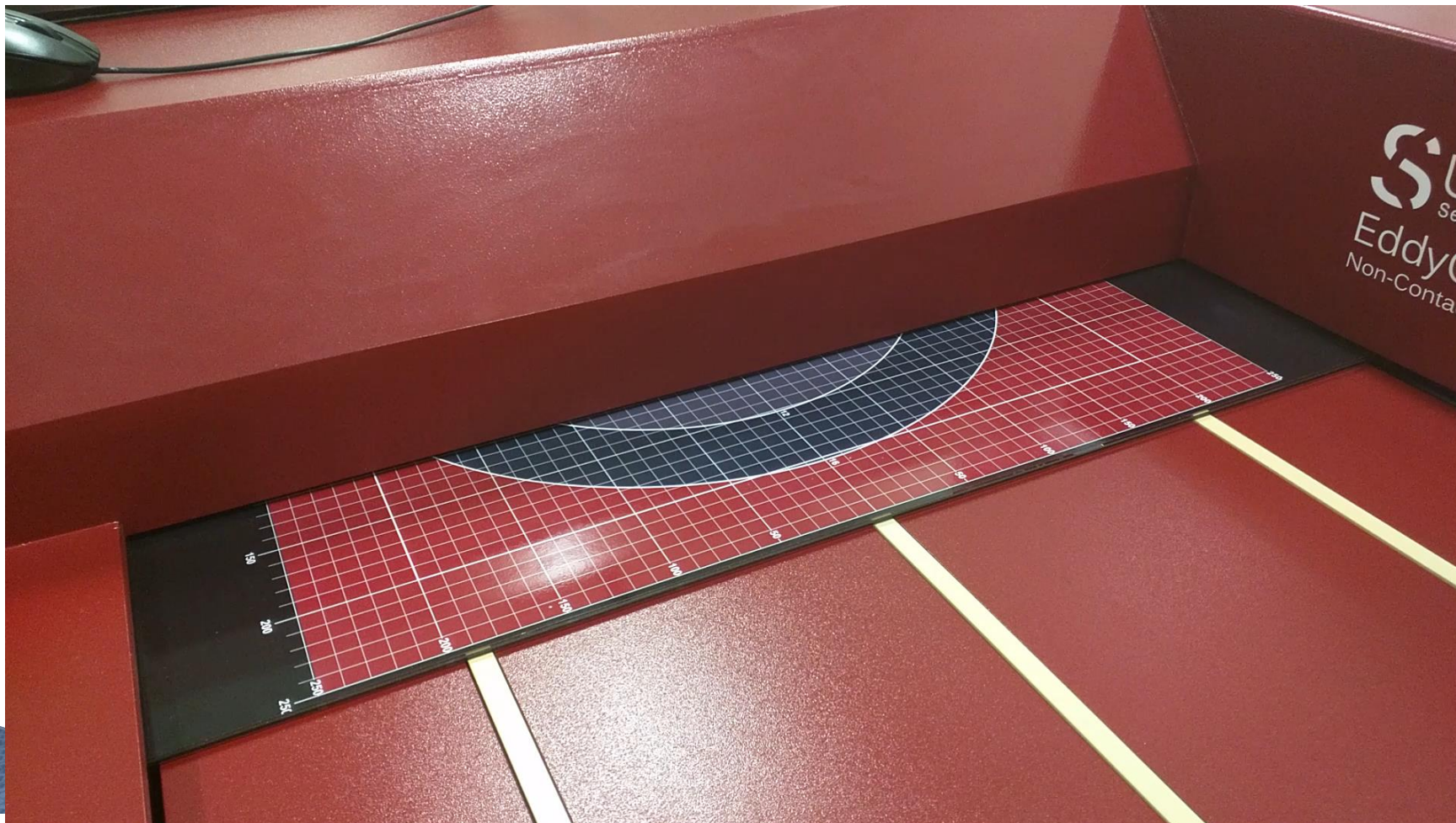
Manual mapping and export function

# Simultaneous Manual Mapping of Sheet Resistance and Optical Transparency of Large Area Graphene (LAG)



Watch movie on youtube [here](#).

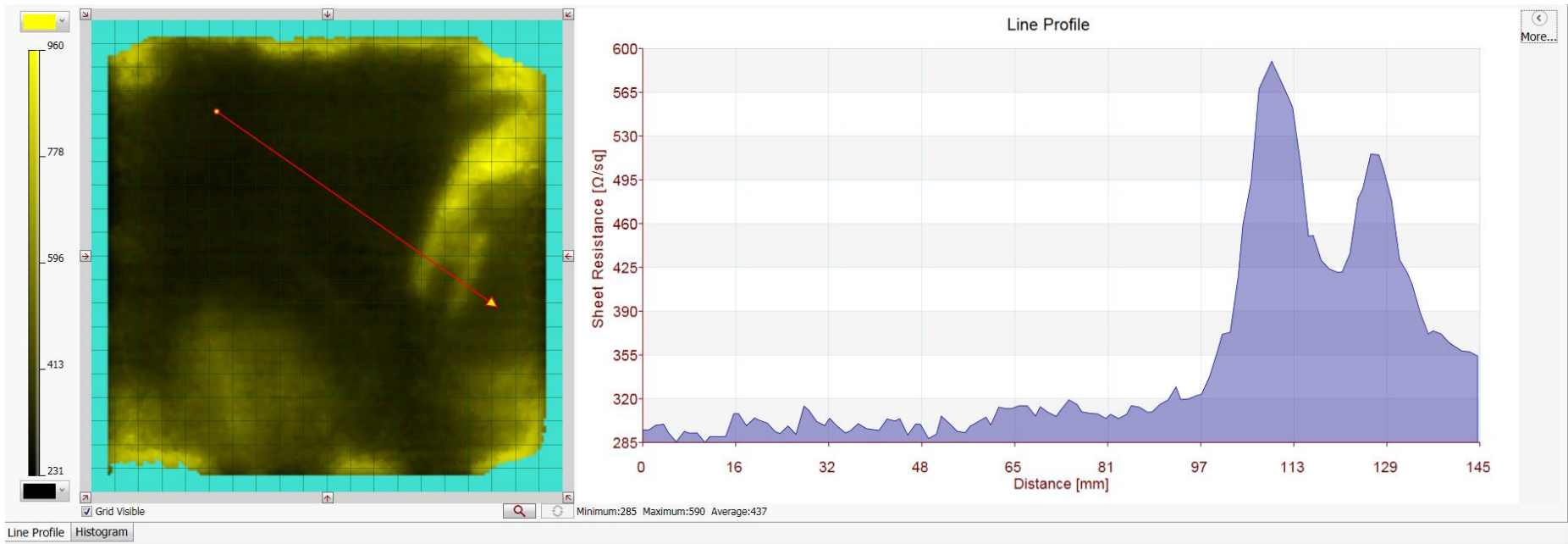
# Demonstration of Sheet Resistance Imaging of Large Area Graphene





# Sheet Resistance Imaging Analysis - Defectoscopy

Sheet resistance imaging [ $\Omega/\text{sq}$ ] on 200 x 200 mm

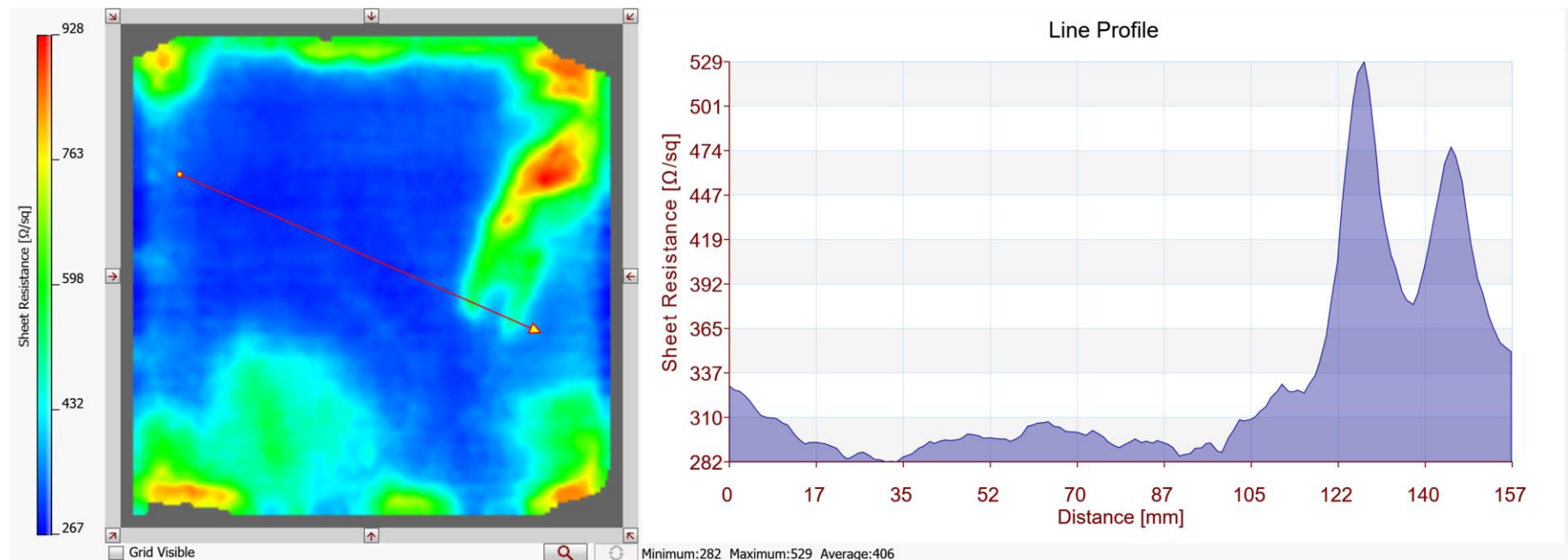






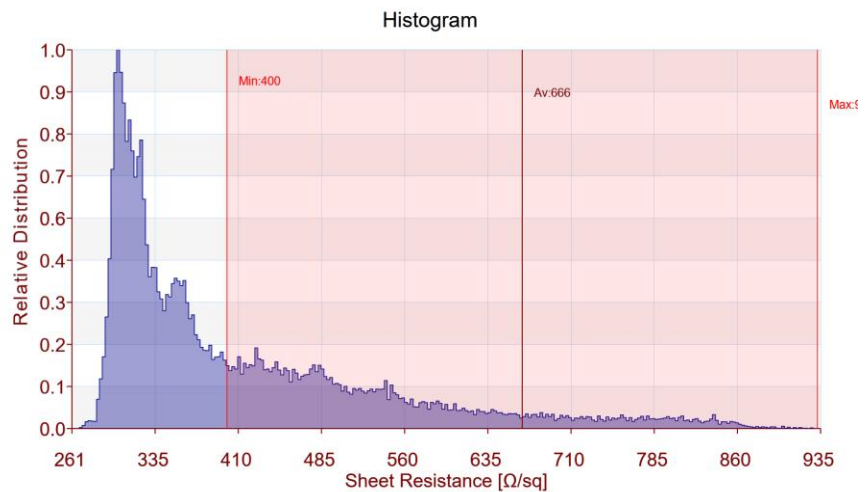
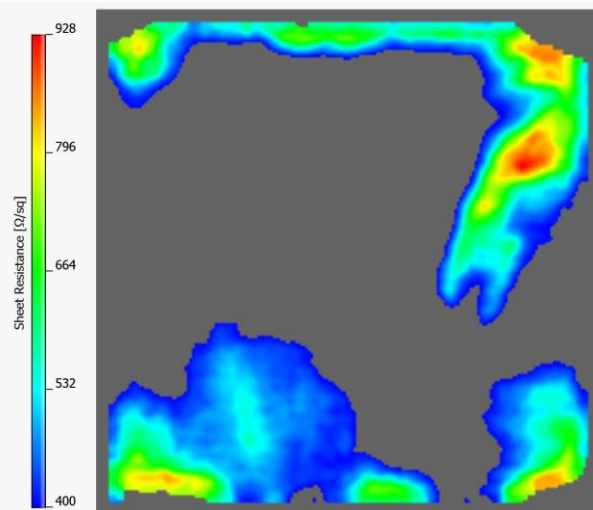
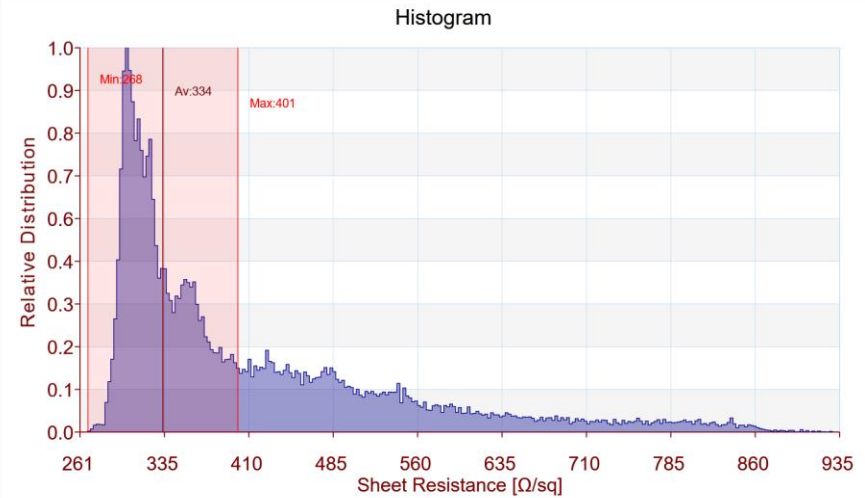
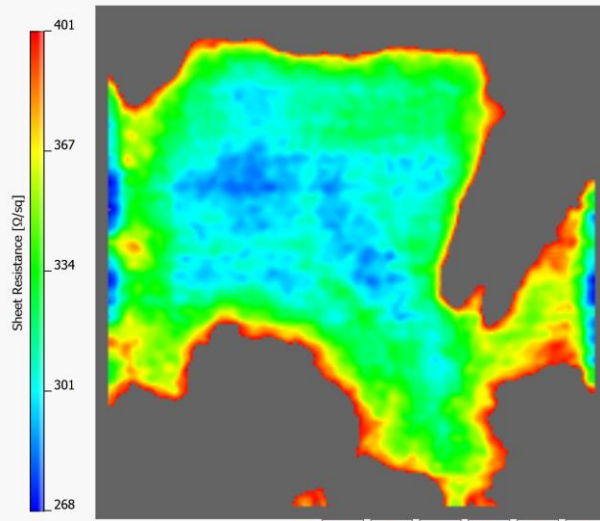
# Sheet Resistance Imaging Analysis - Defectoscopy

Sheet resistance imaging [ohm/sq] on 200 x 200 mm



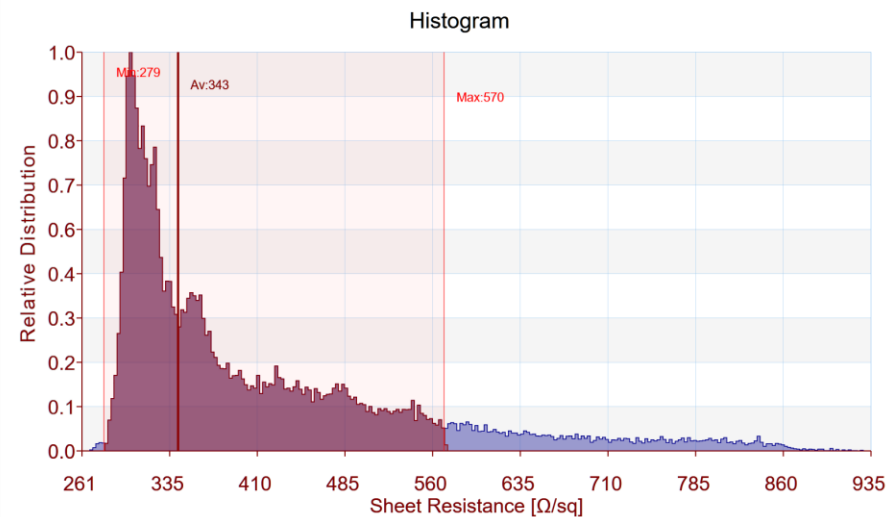
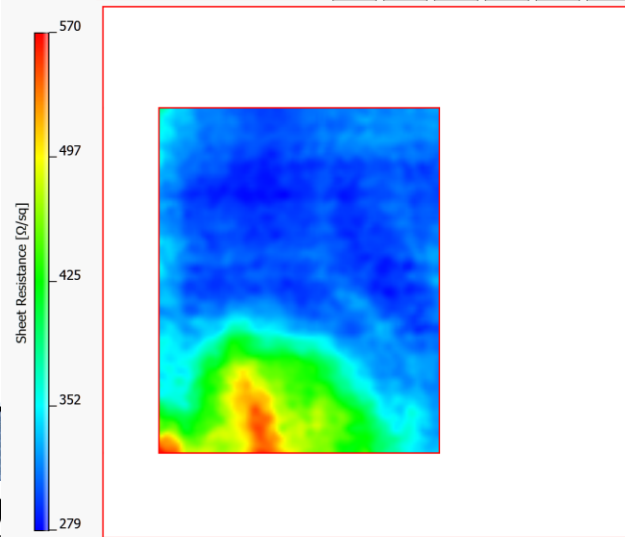
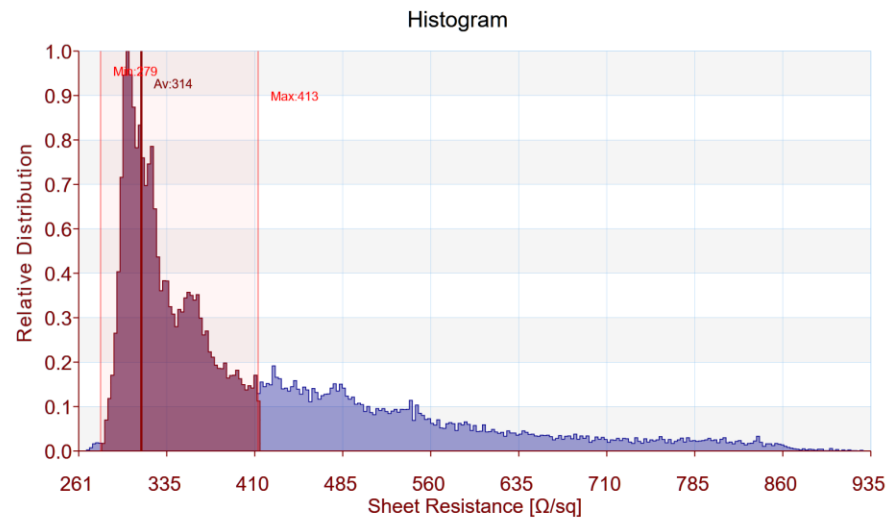
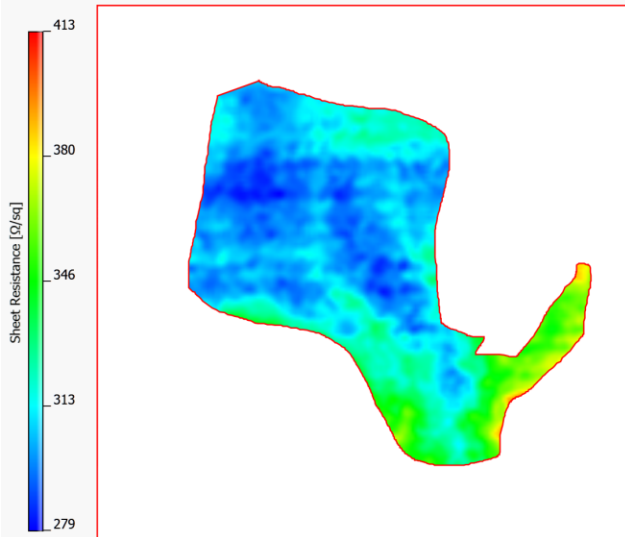


# Sheet Resistance Imaging Analysis - Defectoscopy





# Sheet Resistance Imaging Analysis - Defectoscopy

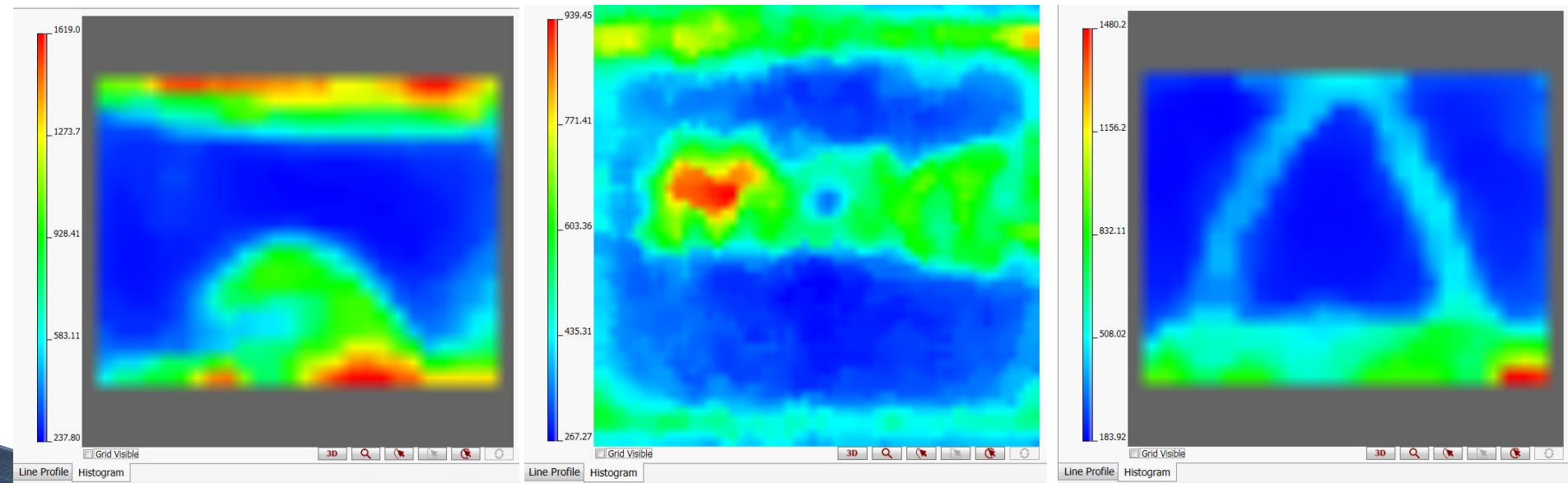




# Missing Graphene, Holes and Cracks

- Defect detection
- Selection of “good areas” for further processing

Sheet resistance mappings [ohm/sq] on ~ A4

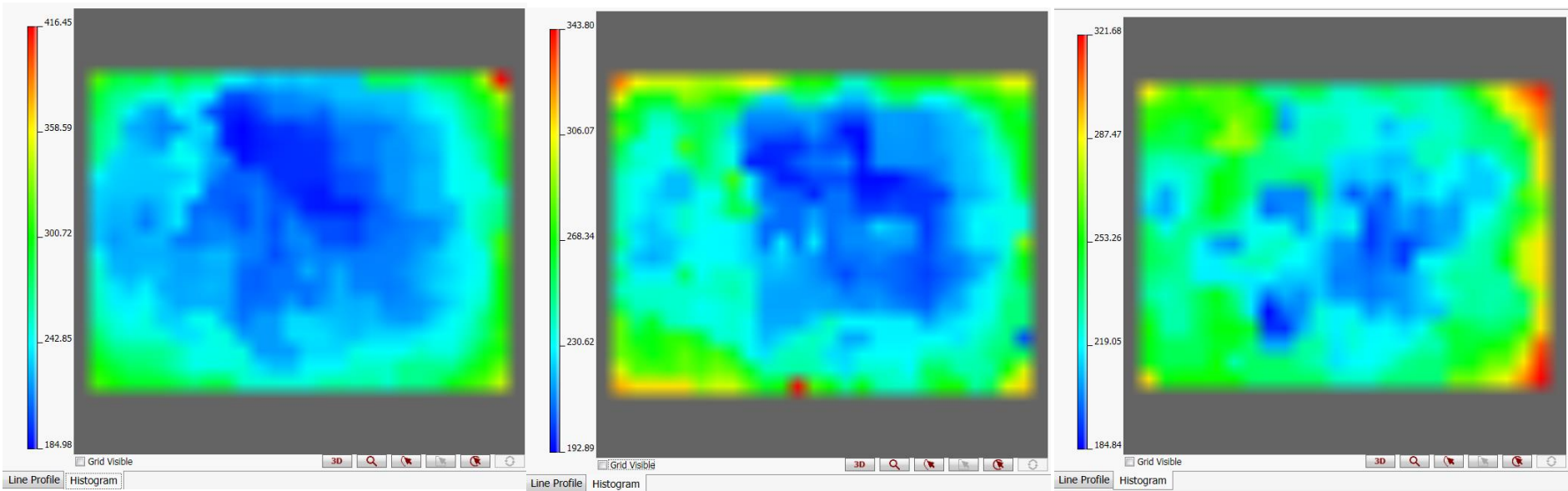




# Small Inhomogeneity

- Homogeneity assessment

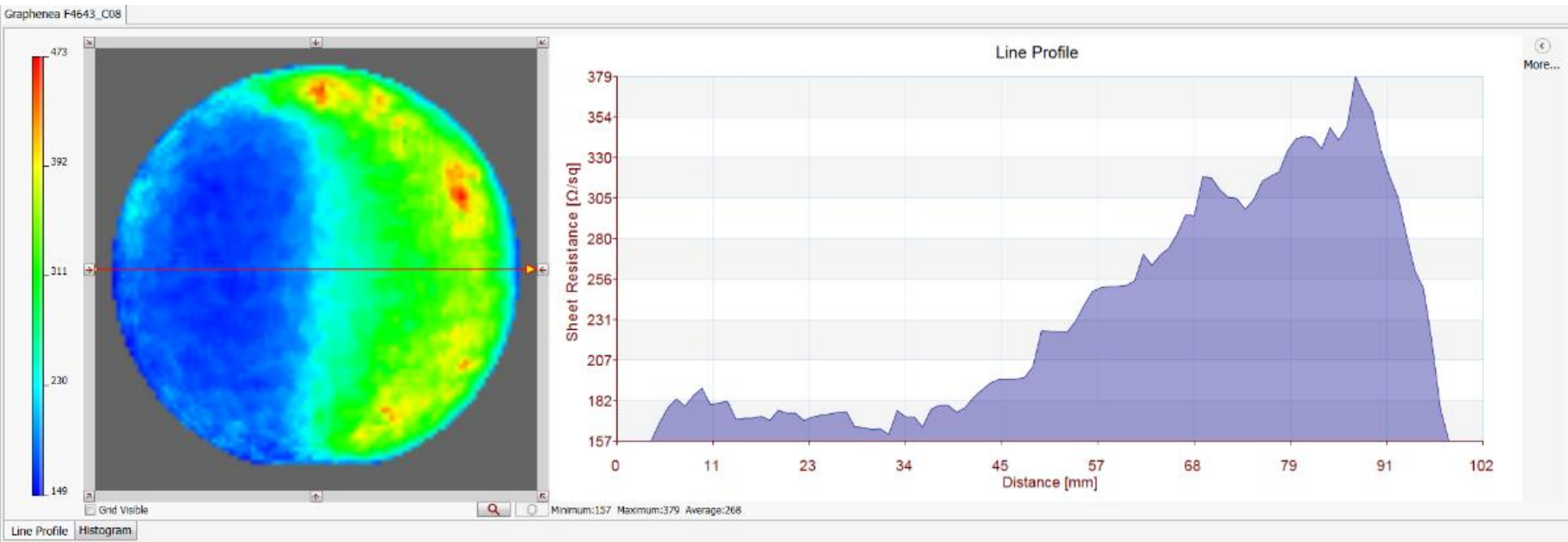
Sheet resistance mappings [ohm/sq] on ~ A4





# Doping Effectivity

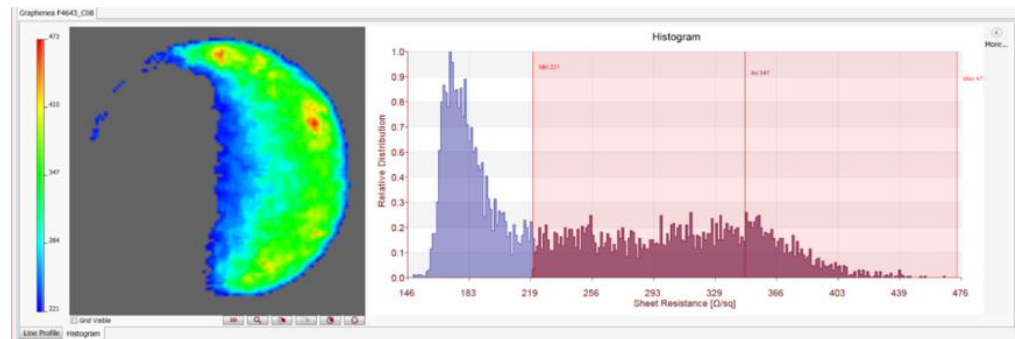
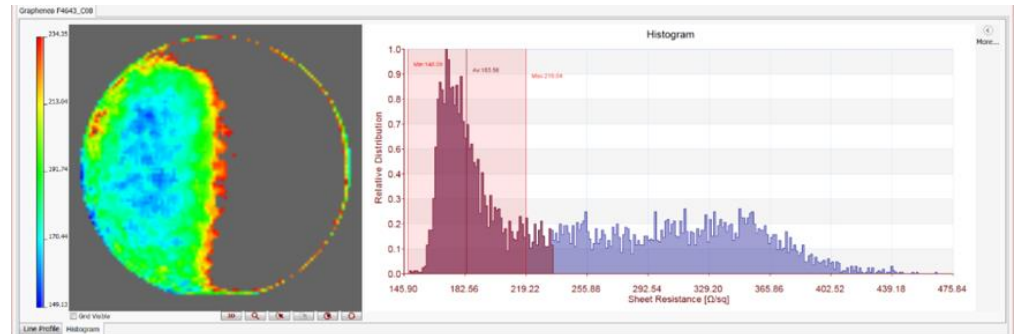
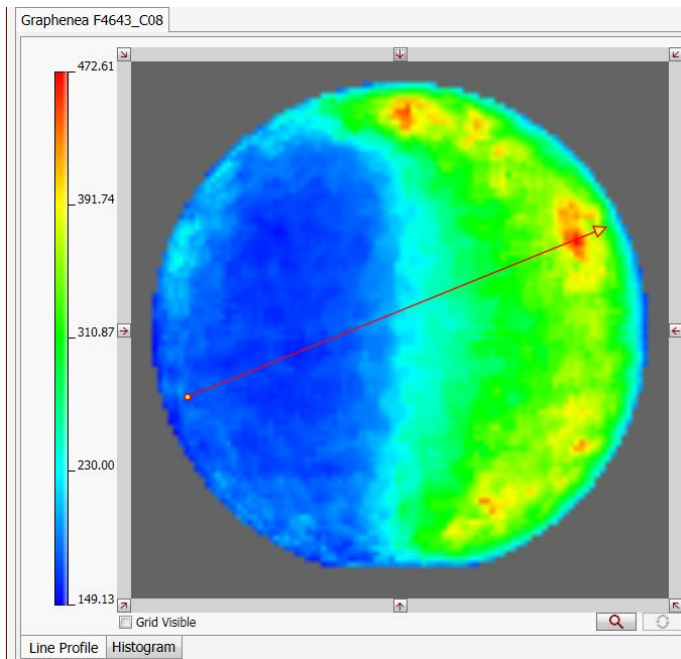
- Doping effectivity
- Doping homogeneity
- Doping stability





# Doping Efficiency Imaging

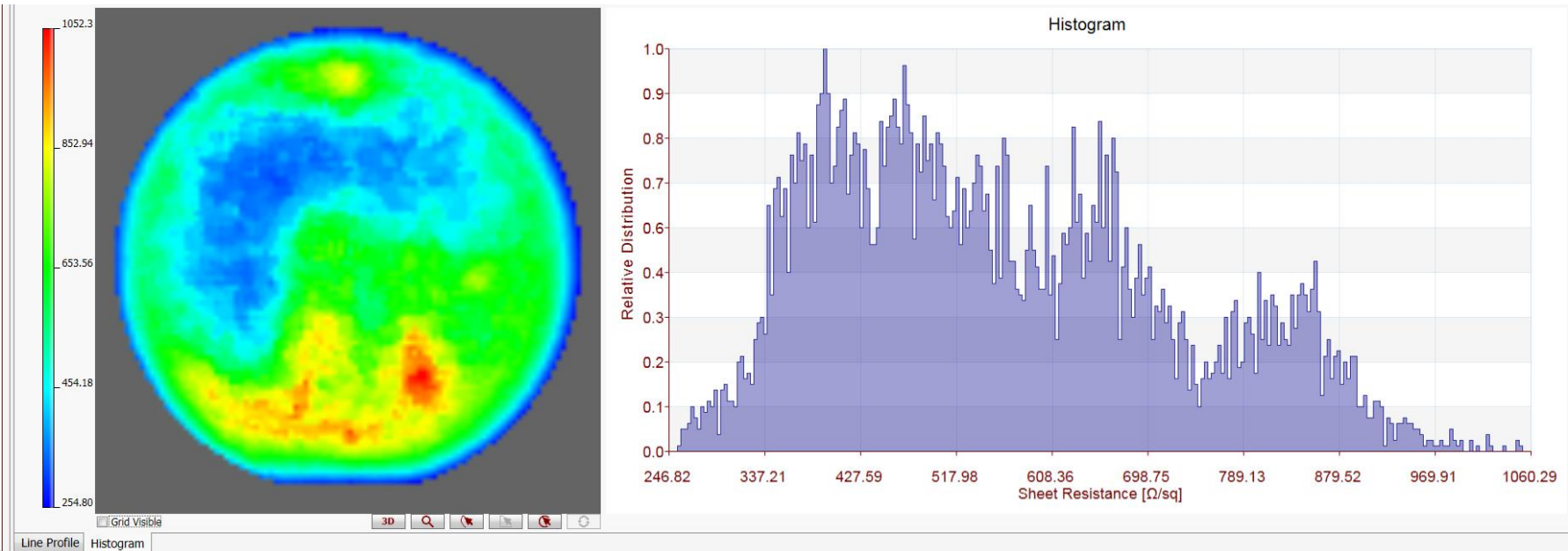
- Inhomogeneous doping





# Sheet Resistance Images – Graphene Mappings

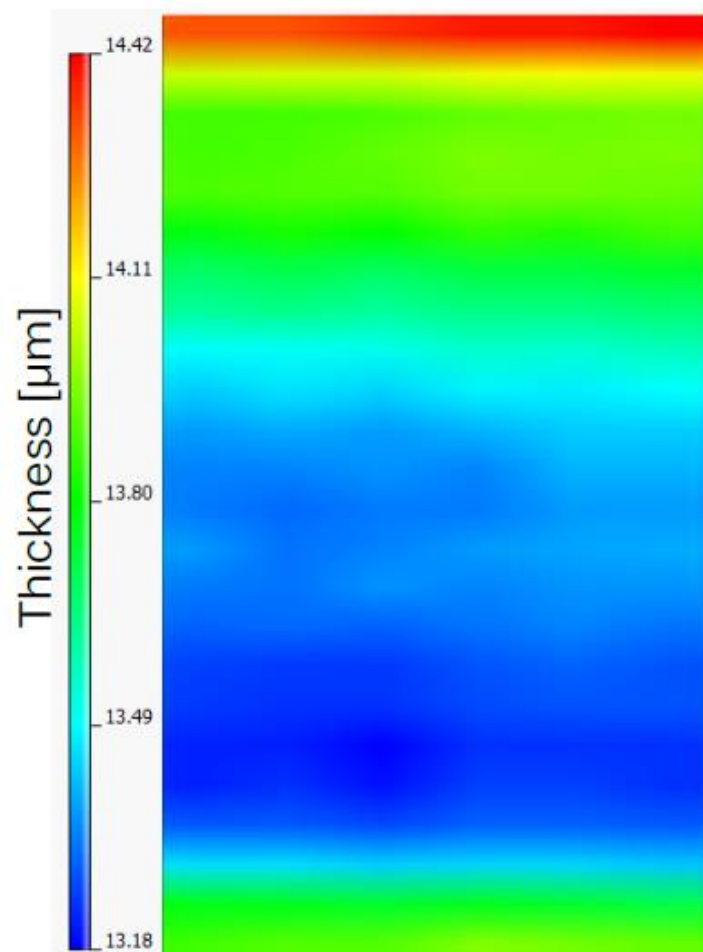
- Graphene with local defects on Wafer
- 4 inch
- Measurement pitch 1 mm x 1mm







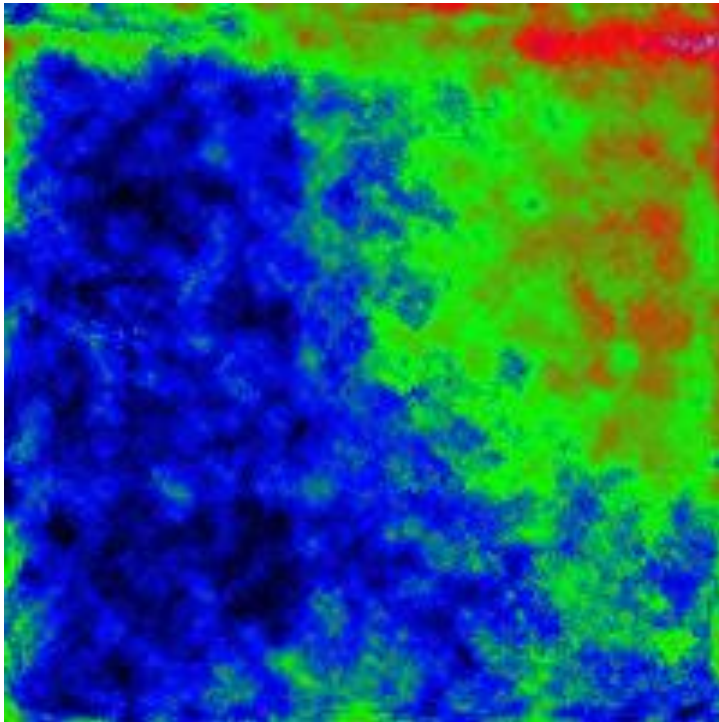
## Graphene Imaging on Copper?



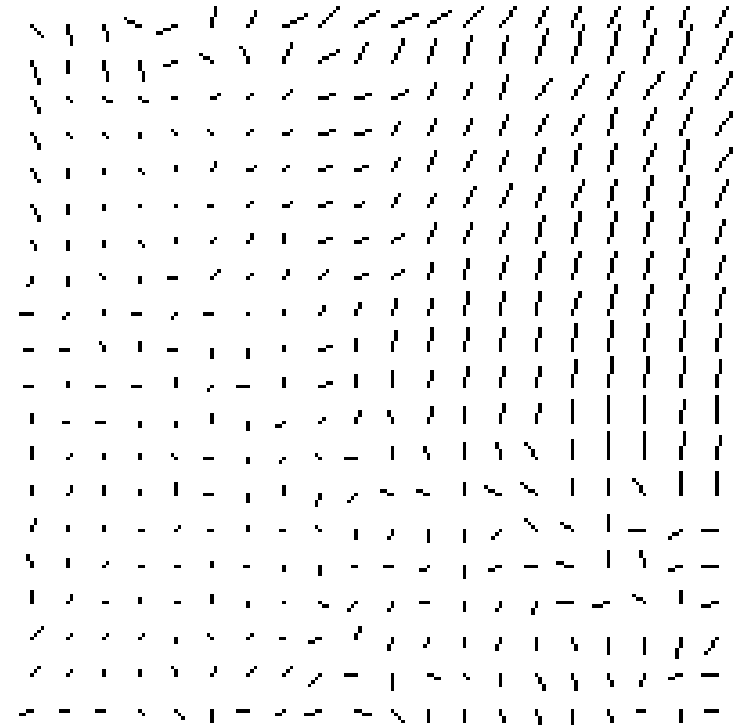


## Anisotropy Imaging of Graphene? – Example on Ag-NW

- 200 x 200 mm [8 inch], Measurement pitch 1 mm x 1mm



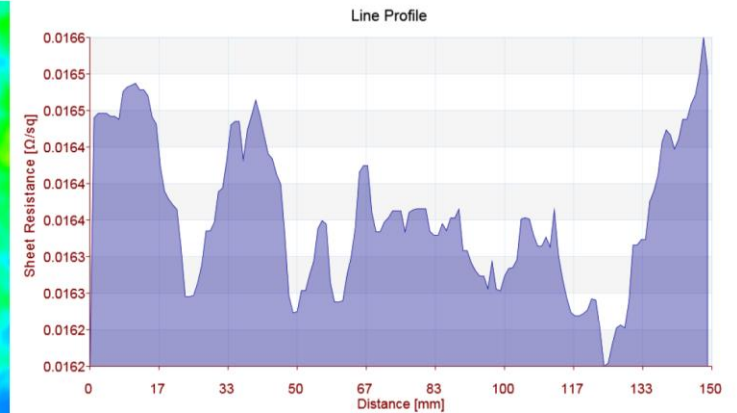
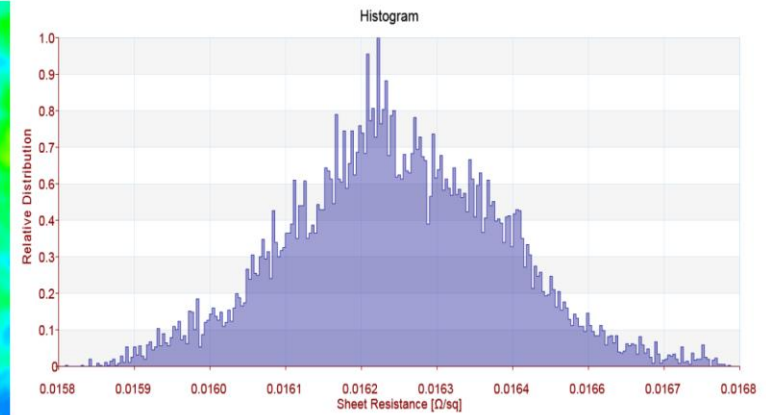
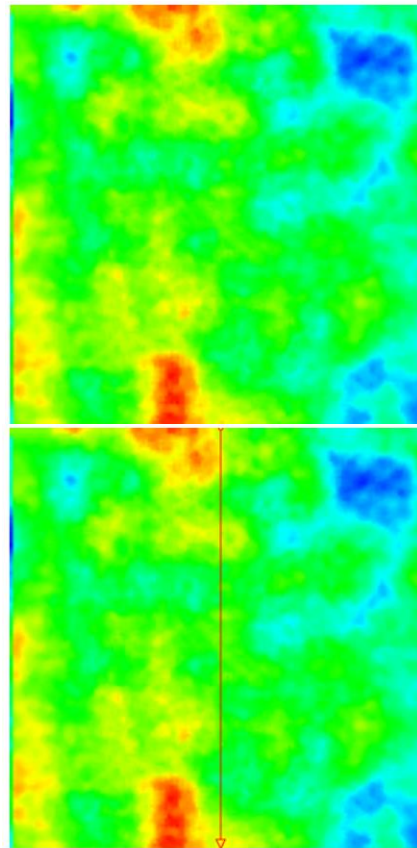
Anisotropy strength(blue=low anisotropy, red=high)



Direction of the least present sheet resistance



# Graphite Imaging





# Inline Testing – A Look into the Graphene Testing Future...

## Inline Sheet Resistance Measurement

- Non-contact
- Real-time
- QA & Process control after
  - Transfer
  - Cleaning
  - Doping
  - Annealing
  - Potentially stacking
  - Final QA





## Demonstration – Future Graphene Inline Testing



[www.sheet-resistance-testing.com](http://www.sheet-resistance-testing.com)

Customized numbers of monitoring lanes  
EddyCus TF inline Series



## Take home messages

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- Applications that require complex or sophisticated properties are a focus for Graphene
- TCM was introduced as one example
- There are various characteristics of Graphene – most of them affect electrical performance
- HF eddy current testing provides various benefits for Graphene characterization
  - Non- contact, non-destructive, imaging, defect density assessment
- Defectoscopy by imaging solution provides insights to many quality aspects
- Control of defect density is a key factor for successful application
- Quality assurance and process control needs to be considered along the process chain →  
Deposition, after transfer, doping, annealing, aging, cleaning, application integration



## Any Questions?

### ► Special thanks to

- **FEP:** Beatrice Beyer, David Wynands, Falk Schütze, André Philipp, Susan Mühl, Jan Hesse, Tae-Hyun Gil
- **Graphenea:** Amaia Pesquera, Amaia Zurutuza
- **CEA:** Jean Dijon, Hélène Le poche
- **SURAGUS GmbH:** Marcus Klein, Richard Kupke
- **Technical University of Denmark:** Tim Booth, Patrick R. W.
- **IOM:** Lutz Prager

▪ **EC:** The research leading to these results has received funding from the European Union Seventh Framework Programme FP7/2007- 2013 under grant agreement n° 604000 (GLADIATOR)





# For Questions and Requests Please Feel Free to Contact us...

- SURAGUS is keen to contribute and participate in graphene application developments
- Please feel free to share your ideas!!

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## Or Visit us in Dresden – e.g. at Graphene 2018

